CLAIMS

1. A photoelectrode material characterized by comprising a composition including silicon oxide.

2. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is synthetic quartz.

3. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is fused quartz glass.

4. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is soda-lime glass.

5. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is non-alkali glass.

6. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is borosilicate glass.

7. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is glass fiber.

8. The photoelectrode material according to claim 1, characterized in that the composition including silicon oxide is treated with halogen acid.

9. The photoelectrode material according to claim 8, characterized in that said halogen acid is hydrofluoric acid.

10. The photoelectrode material according to claim 8, characterized in that said halogen acid is hydrochloric acid.

11. A photocell material characterized by comprising a composition including silicon oxide.

12. The photocell material according to claim 11, characterized in that the composition including silicon oxide is synthetic quartz.

13. The photocell material according to claim 11, characterized in that the composition including silicon oxide is fused quartz glass.

14. The photocell material according to claim 11, characterized in that the composition including silicon oxide is soda-lime glass.

15. The photocell material according to claim 11, characterized in that the composition including silicon oxide is non-alkali glass.

16. The photocell material according to claim 11, characterized in that the composition including silicon oxide is borosilicate glass.

17. The photocell material according to claim 11, characterized in that the composition including silicon oxide is glass fiber.

18. The photocell material according to claim 11, characterized in that the composition including silicon oxide is treated with halogen acid.

19. The photocell material according to claim 18, characterized in that said halogen acid is hydrofluoric acid.

20. The photocell material according to claim 18, characterized in that said halogen acid is hydrochloric acid.

AMENDED CLAIMS

(Accepted at the International Bureau on January 20, 2011)

1. A photoelectrode material characterized by comprising a composition consisting primarily of silicon oxide.

2. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is synthetic quartz.

3. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is fused quartz glass.

4. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is soda-lime glass.

5. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is non-alkali glass.

6. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is borosilicate glass.

7. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is glass fiber.

8. The photoelectrode material according to claim 1, characterized in that the composition consisting primarily of silicon oxide is treated with halogen acid.

9. The photoelectrode material according to claim 8, characterized in that said

halogen acid is hydrofluoric acid.

10. The photoelectrode material according to claim 8, characterized in that said halogen acid is hydrochloric acid.

11. A photocell material characterized by comprising a composition consisting primarily of silicon oxide.

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15. The photocell material according to claim 11, characterized in that the composition consisting primarily of silicon oxide is non-alkali glass.

16. The photocell material according to claim 11, characterized in that the composition consisting primarily of silicon oxide is borosilicate glass.

17. The photocell material according to claim 11, characterized in that the composition consisting primarily of silicon oxide is glass fiber.

18. The photocell material according to claim 11, characterized in that the composition consisting primarily of silicon oxide is treated with halogen acid.

19. The photocell material according to claim 18, characterized in that said halogen acid is hydrofluoric acid.

20. The photocell material according to claim 18, characterized in that said halogen acid is hydrochloric acid.

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